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(54) Title: SCANNING RADICAL SENSOR USABLE FOR MODEL TRAINING

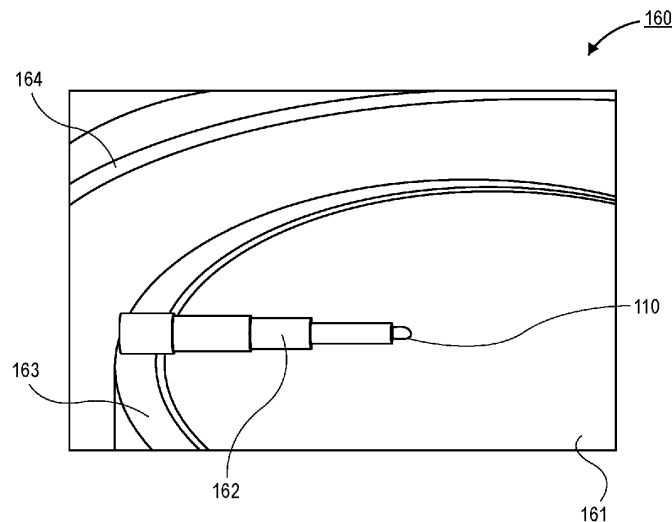


FIG. 1A

(57) Abstract: In an embodiment, a plasma processing tool with an extendable probe is described. In an embodiment, the plasma processing tool comprises a chamber, and a pedestal for supporting a substrate. In an embodiment, an edge ring is around a perimeter of the pedestal. Additionally, a sensor at an end of a probe is provided. In an embodiment, the probe is configured to extend over the pedestal.

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